





A RF plasma oxygen ion source on NanoSIMS for subcellular trace element detection

Dirk Schaumlöffel¹, Julien Malherbe¹, Étienne Gontier² François Hillion³, François Horréard³, Dirk Dobritzsch⁴

¹Université de Pau et des Pays de l'Adour / CNRS
 Institut des Sciences Analytiques et de Physico-Chimie
 pour l'Environnement et les Matériaux, UMR 5254 IPREM/LCABIE, Pau, France
 ²Bordeaux Imaging Center, Pôle d'imagerie électronique, Bordeaux, France
 ³CAMECA, 29 Quai des Grésillons, Gennevilliers, France
 ⁴Martin-Luther-Universität Halle-Wittenberg
 Institut für Biochemie und Biotechnologie, Abteilung Pflanzenbiochemie, Halle (Saale), Germany

The 7th International NanoSIMS user meeting "NanoSIMS & correlative microscopy: exploring physical and biochemical boundaries" Leipzig, Germany, 22-24th of August 2017

Equipex MARSS project





NanoSIMS delivery and installation in Pau (March – June 2017)







A new RF plasma O⁻ primary ion source on NanoSIMS



Hyperion[™] source manufactured by Oregon Physics (Hillsboro, OR)

Schematic view of the RF plasma O⁻ primary ion source



Source diameter : 70 - 80 μ m (manufacturer specification 35-50 μ m) Brightness: ~ 100 mA×cm⁻²×sr⁻¹ at 8 kV

Oxygen ion distribution of the primary beam using a Wien filter located after the source



O⁻ ions represent approximately 88% of the distribution

Determination of the size of the O⁻ primary ion beam (probe size)



Si oxide grain sample over Al substrateImage size:3 x 3 µmProbe intensity:0.15 pA

Line scan (left image) showing **intensity variation** from **16 to 84 %:** determination of **probe size** (resolution)

Comparison with Duoplasmatron and Cs primary ion sources

RF plasma source, 0.15pA

Duoplasmatron Source, 0.1pA



Cs⁺ source, 0.17pA

Comparison of the sample current density for the Cs⁺ , O⁻ duoplasmatron and O⁻ RF sources



Current density at the sample 16 times higher with RF plasma source

Achievable lateral resolution improved by a factor of **3**

Comparison of normalized counts for selected elements using O⁻ duoplasmatron and O⁻ RF sources

Count rate normalized to acquisition time, probe size, and isotope abundance



Increased secondary ion yield **mathe increased apparent element sensitivity (by factor 5 to 45)**

Bioimaging with NanoSIMS

Use of the <u>RF plasma oxygen primary ion source</u> for the localization of major (**Na, Ca, P**) and trace (**Fe, Cu,**) elements in plant (algae) cells

Application to a model organism



Model system: Chlamydomonas reinhardtii

- single celled green micro algae
- commonly found in soil and fresh water
- exists in different strains
- model organism to study cell response to metal stress



- F : Flagella
- V : Vacuoles N : Nucleus
- Nu : Nucleolus
- C : Chloroplast
- T : Thylakoid
- P : Pyrenoid
- S : Starch



TEM analysis (70 nm thin section) resolution down to 1 nm

Cs⁺ source

256pix 8 μ m 1 pA 10ms/pix



[min-max]



[800-1500]



[75-500]



[0-14]



[14-60]

O⁻ RF plasma source

256pix FOV 8µm 1,4pA 10ms/pix



[min-max]



O⁻ Duoplasmatron source

256pix FOV 8µm 1,5pA 8ms/pix



[min-max]



256pix FOV 8µm 1,5pA 15ms/pix



NanoSIMS analysis of Chlamydomonas reinhardtii cells

Comparison conventional Duoplasmatron O⁻ ion source and new RF plasma O⁻ ion source

Duoplasmatron O- ion source

²³Na

⁴⁰Ca

Min

300 nm thin sections

relative intensity: Max

20 x 20 µm 11 min (Duo) 5.5 min (RF) 256x256 pixel 1 plane



00

5 µm





Lateral resolution in biological cell imaging (C. reinhardtii)

1.2

1.4

Line scans on Ca containing vacuoles/acidocalcisomes

O⁻ Duoplasmatron

40Ca*



2.5pA ; FOV 20µm ; 256pix ; 10ms/pix

1.5pA ; FOV 8µm ; 256pix ; 8ms/pix

⁴⁰Ca



O⁻ RF plasma

86pA ; FOV 20µm ; 256pix ; 5ms/pix





1.4pA ; FOV 8µm ; 256pix ; 10ms/pix





[min-max]

Subcellular element imaging by NanoSIMS (RF plasma O⁻ ion source)

Pyrenoid with starch plates

Granules ?



Single cell imaging: 12 x 12 µm, 22 min, 512x512 pixel, 5 ms/pixel 2 planes

Scheme of a Acidocalcisome



R. Docampo, W. de Souza, K. Miranda, P. Rohloff, S. N. J. Moreno, Nature Reviews 2005, 3, 251-261

Correlative imaging TEM - NanoSIMS



RF plasma O⁻ source: 10 × 10 µm FOV; 256 × 256 pix; dwell time 25 ms/pix; 27 min.

Conclusions: advantages of the new RF plasma O⁻ source

- Higher beam density = better sensitivity for metals (Ca, Fe, Cu, Mn....)
- **Higher lateral resolution** than conventional oxygen sources = sharper images enabling the observation of smaller details
- **Less maintenance** = less instrument downtime
- **Stability:** < 1.6 % variation of primary current over 14h
- High resolution images of **trace elements in biological cell** opens new application fields

Acknowledgements

University of Pau/CNRS-IPREM

Florent Penen Marie-Pierre Isaure Anne-Laure Bulteau PhD student Lecturer CNRS researcher (now ENS Lyon)

University Potsdam (Germany)

Tanja Schwerdtle Julia Bornhorst (neurotoxicology) (neurotoxicology

- French ANR-EQUIPEX program (Equipment of Excellence)
 Project: ANR-11-EQPX-0027 Mass Spectrometry Center MARSS
- STAVENIR

- CAMECA
- French Ministry of Research (PhD fellowship)
- Campus France DAAD

Thank you for your attention